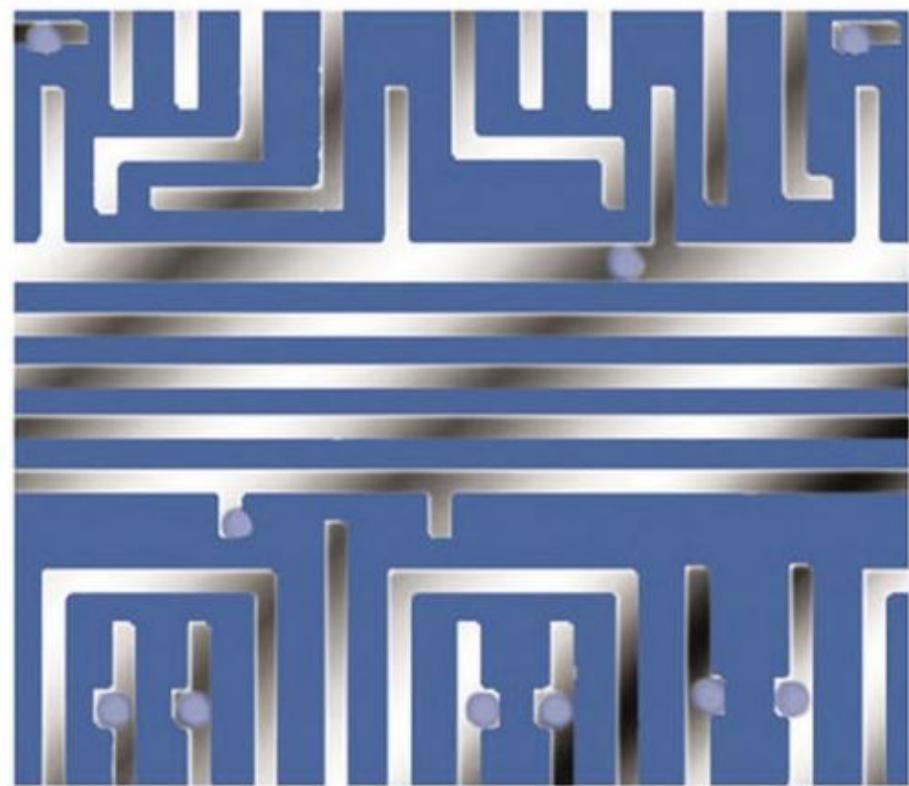


Joseph M. Steigerwald,  
Shyam P. Murarka, Ronald J. Gutmann

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# Chemical Mechanical Planarization of Microelectronic Materials



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**JOSEPH M. STEIGERWALD  
SHYAM P. MURARKA  
RONALD J. GUTMANN**



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**Library of Congress Card No.:**  
Applied for

**British Library Cataloging-in-Publication Data:**  
A catalogue record for this book is available

**Bibliographic information published in Die Deutsche Bibliothek:**  
Die Deutsche Bibliothek lists this publication  
in the Deutsche Bibliographie; detailed bibliographic data is available in

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© 2004 WILEY-VCH Verlag GmbH &

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Printed in the Federal Republic of Germany  
Printed on acid-free paper

**Printing** Strauss GmbH, Mörlenbach  
**Bookbinding** Litges & Dopf Buchbinderei

**ISBN-13:** 978-0-471-13827-3  
**ISBN-10:** 0-471-13827-4



WILEY-VCH Verlag GmbH & Co. KGaA

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